

a1 9. (Amended) The photolithographic mask of claim 1, wherein the second layer is Hydrogen Silsesquioxane.

a2 16. (Amended) The photolithographic mask of claim 15, wherein the second layer is Hydrogen Silsesquioxane.

a3 36. (Amended) The photolithographic system of claim 35, wherein the second layer is Hydrogen Silsesquioxane.

REMARKS

Entry of the above amendments before first action is respectfully requested. It is believed that no new matter was introduced by amending the specification. In particular, the Applicants point out that the material FOX - 11, disclosed on page 6, line 12 of the application, is Hydrogen Silsesquioxane.

In view of these amendments, consideration and allowance of all claims in the present application are respectfully requested. Of course, the Examiner is invited to telephone the undersigned attorney, if necessary, so that prosecution of this application may be expedited.

Respectfully submitted,

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